

Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet

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of

1

Complete if Known

Application Number	10/729,169
Filing Date	December 4, 2003
First Named Inventor	Robert David ALLEN et al.
Art Unit	1713
Examiner Name	Unassigned
Attorney Docket Number	ARC920030103US1

U.S. PATENT DOCUMENTS

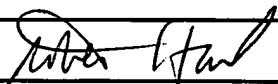
Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
RM	AR	4,356,296	10/26/82	Griffith et al.	X	X	
	AS	4,365,049	12/21/82	Tsunoda et al.			
	AT	4,452,998	6/5/84	Griffith et al.			
	AU	6,027,856	2/22/00	Nozaki et al.			
	AV	6,074,801	6/13/00	Iwasa et al.			
	AW	6,106,998	8/22/00	Maeda et al.			
	AX	6,140,010	10/31/00	Iwasa et al.			
	AY	6,146,806	11/14/00	Maeda et al.			
YU	AZ	6,319,650	11/20/01	Gelorme et al.			
	BA	Serial No. 10/604,082	Filed 6/25/03	Hinsberg et al.			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document No.	Publication Date	Country	Class	Subclass	T
RM	BB	JP 61281116 A	11/12/86	Japan			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
RM	BC	ALLEN et al. (1997), "Deep-UV Resist Technology: The Evolution of Materials and Processes for 250-nm Lithography and Beyond," <i>Handbook of Microlithography, Micromachining, and Microfabrication Volume I: Microlithography</i> , Chapter 4, pp. 321-375, P. Rai-Choudhury, Editor, SPIE Optical Engineering Press..	
	BD	FEDYNYSHYN et al. (2001), "High Resolution Fluorocarbon Based Resist for 157-nm Lithography," <i>Advances in Resist Technology And Processing XVIII, Proceedings of SPIE 4345:296-307</i> .	
	BE	KODAMA et al. (2002), "Synthesis of Novel Fluoropolymer for 157nm Photoresists by Cyclo-Polymerization," <i>Advances in Resist Technology and Processing XIX, Proceedings of SPIE 4690:76-83</i> .	
	BF	REICHMANIS et al. (1991), "Chemical Amplification Mechanisms for Microlithography," <i>Chem. Mater.</i> 3(3):394-407	
CM	BG	URRY et al. (1968), "Multiple Multicenter Reactions of Perfluoro Ketones with Olefins," <i>The Journal of Organic Chemistry</i> 33(6):2302-2310.	

Examiner
Signature

Date
Considered

11/2/06

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Examiner Initials*	Cite No.	Document No.	Issue Date or Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date if Appropriate
RM	AA	5,391,587	2/21/95	Wu			
	AB	5,665,527	9/9/97	Allen et al.			
	AC	5,919,597	7/6/99	Sinta et al.			
	AD	6,037,097	3/14/00	Bucchignano et al.			
	AE	6,043,003	3/28/00	Bucchignano et al.			
RM	AF	6,265,135	7/24/01	Kodama et al.			
	AG	Serial No. 10/716,785	Filed 11/19/03	Angelopoulos et al.			
	AH	Serial No. 10/729,452	Filed 12/4/03	Robert David Allen et al.			

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Foreign Patent Document No.	Publication Date	Country	Class	Subclass	T
RM	AI	WO 01/86352	11/15/01	PCT			
	AJ	WO 02/079287	10/10/02	PCT			
RM	AK	WO 03/040827	5/15/03	PCT			

OTHER DOCUMENTS — NONPATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), Title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
MM	AL	BAE et al. (2003), "Rejuvenation of 248 nm Resist Backbones for 157 nm Lithography," <i>Journal of Photopolymer Science and Technology</i> 14(4):613-620.	
	AM	HINSBERG et al. (2000), "Effect of Resist Components on Image Spreading During Postexposure Bake of Chemically Amplified Resists," <i>Advances in Resist Technology and Processing XVII, Proceedings of SPIE</i> 3999:148-160.	
	AN	HINSBERG et al. (2003), "Extendibility of Chemically Amplified Resists: Another Brick Wall?," <i>Advances in Resist Technology and Processing XX, Proceedings of SPIE</i> 5039:1-14.	
	AO	HOULE et al. (2000), "Determination of Coupled Acid Catalysis-Diffusion Processes in a Positive-Tone Chemically Amplified Photoresist," <i>J. Vac. Sci. Technol. B</i> 18(4):1874-1885.	
	AP	ITO et al. (2001), "Polymer Design for 157 nm Chemically Amplified Resists," <i>Advances In Resist Technology And Processing XVIII, Proceedings Of SPIE</i> 4345:273-284.	
MM	AQ	KUNZ et al. (2001), "Experimental VUV Absorbance Study of Fluorine-Functionalized Polystyrenes," <i>Advances in Resist Technology and Processing XVIII, Proceedings of SPIE</i> 4345:285-295.	

Examiner Signature	<i>Robert David Allen</i>	Date Considered	11/2/04
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